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REMARKS

Claims 26, 28-30, and 32-48 are pending herein.

1. Claims 26-46 were rejected under 35 U.S.C. 112, second paragraph, as being indefinite. The language relating to average texture has been removed from claims 26 to overcome this rejection. Accordingly, withdrawal of the §112, second paragraph rejection is respectfully requested.

2. Claims 26, 28-30, and 32-46 were rejected under 35 U.S.C. 103(a) as being unpatentable over Iijima et al. (2001/0006042) in view of Vaidya et al. (US 5076203). This rejection is respectfully traversed for the following reasons.

The claimed invention is drawn to a process for continuous deposition of a coating of an HTS tape. The claimed invention particularly calls for injecting gas through a plurality of gas channels onto a substrate. The claims have been amended to clarify extending the plurality of gas channels to the first surface of the substrate block and terminating the gas channels at positions spaced apart from each other along the first surface. Applicants have shown that injecting gas directly onto the substrate, instead of into the deposition chamber from another location, reduces the average texture of the buffer layer at least about 3 degrees.

While the PTO has relied upon Iijima et al. to allegedly teach the main features of the claimed invention, Iijima et al. do not disclose injecting gas through gas channels of the substrate block. The PTO has apparently relied upon Vaidya et al. to allegedly overcome this deficiency.

Vaidya et al fail to disclose, suggest, or remotely enable translating the substrate along a surface of the substrate block, wherein the gas channels extend to the surface terminate at positions spaced apart from each other along the surface. Rather, Vaidya et al disclose injecting gas through a porous substrate block (Figs 7-10 and Col 6 lines 5-42). Vaidya et al. do not disclose or even remotely suggest incorporation of gas channels

extending through the substrate block to terminate at a surface of the substrate block, at positions spaced apart from each other.

New claim 48 recites even further patentable subject matter over claim 26, notably reciting that the plurality of gas channels are open and unfilled. Not only do Vaidya et al. fail to disclose or even remotely suggest gas flow channels as noted above, but clearly fail to disclose open, unfilled channels as depicted in FIG. 3 of the present application, for example.

For at least the forgoing reasons in view of the amendments to the present claims, Applicants respectfully submit that the presently claimed invention would not have been anticipated by Iijima et al. in view of Vaidya et al. Accordingly, withdrawal of the Section 103 rejection over Iijima et al. in view of Vaidya et al. is respectfully requested.

Applicants respectfully submit that the present application is now in condition for allowance. Accordingly, the Examiner is requested to issue a Notice of Allowance for all pending claims.

Should the Examiner deem that any further action by the Applicants would be desirable for placing this application in even better condition for issue, the Examiner is requested to contact Applicants' undersigned attorney at the number listed below.

The Commissioner is hereby authorized to charge any fees, which may be required, or credit any overpayment, to Deposit Account Number 50-3797.

Respectfully submitted,

Date

2/5/07

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